

Sheet 1 of 1

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

Applicant

Jae-eun Park, et al.

Filing Date

02/19/04

Group Art Unit

2813

(Use several sheets if necessary)

U. S. Patent Documents

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TW	AA	6,090,442	07/18/00	Klaus, et al.	427	255.15	10/02/97
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
							YES NO
	AL						
	AM						
	AN						
	AO						
	AP						
	AQ						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

AR	
AS	
AT	

EXAMINER

T. Nguen

DATE CONSIDERED

12/16/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.



Supt. Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>					Docket Number (Optional) SAM-0483	Application Number 10/782,094	
					Applicant Jae-eun Park, et al.		
					Filing Date 02/19/04	Group Art Unit 2813	
U. S. Patent Documents							
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
<i>TN</i>	AB	5,470,800	11-28-95	Muroyama	437	238	03-26-93
	AC	6,037,275	03-14-00	Wu, et al.	438	780	08-27-98
	AD	6,270,572	08-07-01	Kim, et al.	117	93	08-09-99
	AE	2002/0001974	01-03-02	Chan	438	785	06-20-01
<i>TN</i>	AF	6,391,803	05-21-02	Kim, et al.	438	787	06-20-01
	AG						
	AH						
	AI						
	AJ						
	AK						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO
<i>TN</i>	AL	06132276	05-13-94	Japan	H01L	21/312	
	AM	1 096 042	05-02-01	Europe	C30B	25/02	
	AN	1 003 210	05-24-00	Europe	H01L	21/316	
	AO	10189582	07-21-98	Japan	H01L	21/316	
<i>TN</i>	AP	2001002990	01-09-01	Japan	C09D	183/04	
<i>TN</i>	AQ	1 139 399	10-04-01	Europe	H01L	21/306	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>TN</i>	AR	Klaus, J.W., et al., "Atomic layer controlled growth of SiO₂ films using binary reaction sequence chemistry," American Institute of Physics, 1997, Pages 1092-1094					
	AS						
	AT						
EXAMINER <i>T. Nguyen</i>				DATE CONSIDERED <i>12/16/05</i>			
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1/3/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	Method of Forming Silicon Dioxide Using Siloxane	
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Application Number : 10/782094



Confirmation Number: 4756

First Named Applicant: Jae-Eun Park

Attorney Docket Number: SAM-0483

Art Unit:

Examiner:

Search string: (6664156 or 5037514 or 6534395 or 20020164890 or 20030015764 or 20020047151).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
TM	1	6664156	2003-12-16	Ang, et al.			
TM	2	5037514	1991-08-06	Yamazaki			
TM	3	6534395	2003-03-18	Werkhoven, et al.			

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TM	1	20020164890	2002-11-17	Kwan, et al.			
TM	2	20030015764	2003-01-23	Raaijmakers, et al.			
TM	3	20020047151	2002-04-25	Kim, et al.			

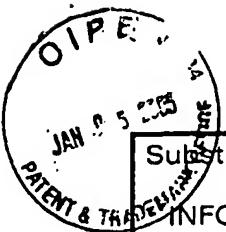
Remarks

Note: Remarks are not for responding to an office action.

part 1 of 1

Signature

Examiner Name	Date
T. NGUYEN	12/16/05



Sheet 1 of 1

Subst. Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) SAM-0483	Application Number 10/782,094		
				Applicant Jae-eun Park, et al.			
				Filing Date 02/19/04	Group Art Unit 2813		
U. S. Patent Documents							
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	BA						
	BB						
	BC						
	BD						
	BE						
	BF						
	BG						
	BH						
	BI						
	BJ						
	BK						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO
<i>TN</i>	BL	2002-0085487	11/16/02	Korea	H01L	21/20	X
	BM						
	BN						
	BO						
	BP						
	BQ						
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
	BR						
	BS						
	BT						
EXAMINER <i>T. Nguyen</i>				DATE CONSIDERED <i>12/16/05</i>			
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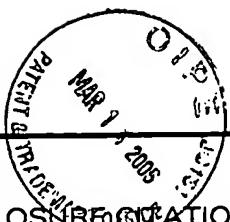
2/2/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	Method for forming silicon dioxide film using siloxane							
Application Number :		10/782094						
Confirmation Number:		4756						
First Named Applicant:		Jae-Eun Park						
Attorney Docket Number:		SAM-0483						
Art Unit:								
Examiner:								
Search string:		(20040096582).pn						
US Published Applications								
Note: Applicant is not required to submit a paper copy of cited US Published Applications								
init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass	
TN	1	20040096582	2004-05-20	Wang, et al.		—	—	
Remarks								
Note: Remarks are not for responding to an office action.								
Part 1 of 1.								
Signature								
Examiner Name				Date				
<i>T. Nguyen</i>				<i>12/16/05</i>				



Sheet 1 of 2

Subst. Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>		Docket Number (Optional) SAM-0483	Application Number 10/782,094
		Applicant Jae-eun Park, et al.	
		Filing Date 02/19/04	Group Art Unit 2813

U. S. Patent Documents

EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
TN	AG	2002/0068466	06/06/02	Lee, et al.	438	765	05/31/01
TN	AH	6,465,371	10/15/02	Lim	438	785	10/15/02
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	AL						
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	AO						
	AP						
	AQ						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	
	AS	
	AT	

EXAMINER <i>T. NEUMAYER</i>	DATE CONSIDERED <i>12/16/05</i>
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Subst. Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Sheet 2 of 2

Docket Number (Optional)	Application Number
SAM-0483	10/782,094
Applicant	
Jae-eun Park, et al.	
Filing Date	Group Art Unit
02/19/04	2813

U. S. Patent Documents

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BA						
BB						
BC						
BD						
BE						
BF						
BG						
BH						
BI						
BJ						
BK						

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
BL							
TN	BM 02-2579	01/10/02	Korea	H01L	21/316		X
TN	BN 02-44422	06/15/02	Korea	H01L	21/20		X
BO							
BP							
BQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

BR	
BS	
BT	

EXAMINER	DATE CONSIDERED
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6/28/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	Method for forming silicon dioxide film using siloxane						
Application Number : 10/782094 Confirmation Number: 4756 First Named Applicant: Jae-eun Park Attorney Docket Number: SAM-0483 Art Unit: Examiner: Search string: (3313792).pn							
US Patent Documents							
Note: Applicant is not required to submit a paper copy of cited US Patent Documents							
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
TM	1	3313792	1967-04-11	Duck, et al.		—	—
Remarks							
Note: Remarks are not for responding to an office action.							
Part 1 of 1.							
Signature							
Examiner Name				Date			
T. NGUYEN				12/16/05			